

202450US0

APR 14 2003

IN THE UNITED STATES PATENT & TRADEMARK OFFICE

IN RE APPLICATION OF:

ATSUSHI SHIOTA ET AL.

SERIAL NO: 09/770,289

FILED: JANUARY 29, 2001

FOR: PROCESS FOR PRODUCING
SILICA-BASED FILM, SILICA-
BASED FILM, INSULATING FILM,
AND SEMICONDUCTOR DEVICE

: GROUP ART UNIT: 1712

:

: EXAMINER: FEELY, M.

RECEIVED
APR 22 2003
TC 1700

AMENDMENT

ASSISTANT COMMISSIONER FOR PATENTS
WASHINGTON, D.C. 20231

SIR:

In response to the Office Action dated December 18, 2002, please amend the
application identified above as follows: